

Our Docket No: 42P10923

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
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                            Donghui Lu                      )     Examiner: Stouffer, Kelly M.  
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                            )  
Application No: 10/811,591                      )     Art Unit: 1792  
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                            )  
Filed: March 29, 2004                              )     Confirmation No: 2696  
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                            )  
For: Enhanced Dielectric Layers Using              )  
                            Sequential Deposition              )  
                            )  
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RESPONSE TO OFFICE ACTION

Mail Stop Amendment  
Commissioner for Patents  
P.O Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed December 3, 2008, Applicants respectfully request the Examiner to enter the following amendment and to consider the following remark.

**CERTIFICATE OF EFS Web**

I hereby certify that this correspondence is being submitted electronically via EFS Web on the date shown below to the United States Patent and Trademark Office.

Date of Deposit: February 10, 2009  
Name of Person Mailing Correspondence: Debbie Casias  
/Debbie Casias/                              / February 10, 2009 /  
Signature                                      Date